

☐ Oral Presentation☒ Poster Presentation

Optimal light-trapping design in thin-film solar cells enhanced with SiO₂/ATO/Graphene layered structure

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Abstract

Antimony doped tin oxide (ATO), as one kind of transparent conductive oxides (TCO), is applied as electrodes in thin film solar cells. On the basis of the traditional glass/TCO structure on top of amorphous silicon thin-film solar cells, graphene is introduced to form the glass/TCO/Graphene and the glass/Graphene/TCO layered structure, which is aimed at both enhancing the optical absorption of thin-film solar cells as an antireflection coating (ARC) and increasing the electrical conductivity as a TCO electrode. In this paper, SiO₂/ATO/Graphene and SiO₂/Graphene/ATO structure are selected for the optimal light-trapping design by using differential evolution method. The effect of graphene is mainly investigated and the thickness of the layers of proposed structure is optimized to enhance the optical absorption of thin-film solar cells to the greatest degree. The theoretical calculation results clearly demonstrate that the proposed SiO₂/ATO/Graphene layered structure is obviously superior to the SiO₂/Graphene/ATO structure, and it can obtain a higher light-trapping enhancement in the whole visible and near-infrared wavelength range because of the graded refractive index distribution profile.

Keywords: Light trapping; thin-film solar cells; graphene; layered structure; differential evolution (DE).

1. Introduction

Amorphous silicon (α -Si) thin-film solar cells have attracted significant interest in research fields because of the low cost, nontoxicity and mature processing technology [1, 2]. Among key materials for α -Si thin-film solar cells, transparent electrodes play an important role in the performance of solar cells because the main features of solar cells, such as fill factor and short-circuit current density, are critically dependent on the series resistance and optical transmittance of the transparent electrodes. Antimony doped tin oxide (ATO), as one kind of transparent conductive oxides (TCO), is applied as electrodes in thin film solar cells. On the basis of the traditional glass/TCO structure on top of amorphous silicon thin-film solar cells, graphene is introduced to form the glass/TCO/Graphene and the glass/Graphene/TCO layered structure, which is aimed at both enhancing the optical absorption of thin-film solar cells as an antireflection coating (ARC) and increasing the electrical conductivity as a TCO electrode [3].

In this paper, SiO₂/ATO/Graphene and SiO₂/Graphene/ATO structure are selected for the optimal light-trapping design by using differential evolution method. The effect of graphene is mainly investigated and the thickness of the layers of proposed structure is optimized to enhance the optical absorption of thin-film solar cells to the greatest degree. The theoretical calculation results clearly demonstrate that the proposed SiO₂/ATO/Graphene layered structure is obviously superior to the SiO₂/Graphene/ATO structure, and it can obtain a higher light-trapping enhancement in the whole visible and near-infrared wavelength range because of the graded refractive index distribution profile.

2. Simulation model

In this paper, a SiO₂/ATO/Graphene structure is proposed as transparent electrodes on amorphous silicon (α -Si) thin-film solar cells. Figure 1 depicts the sketch of a graphene-based thin-film α -Si:H solar cell and geometric structure of SiO₂/ATO/Graphene coatings. In Fig. 1, the graphene transparent electrodes have a layer number of L with a thickness of $L \times 0.34 \text{ nm}$. The proposed SiO₂/ATO/Graphene coatings have two structural parameters including the thickness d for SiO₂ layer and the layer number L of graphene, which need to be optimized.

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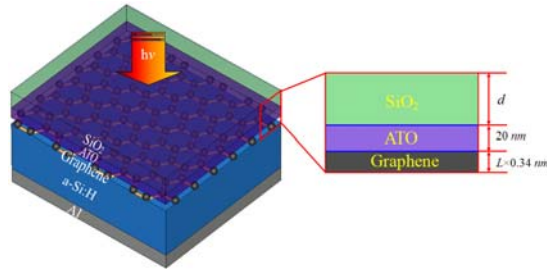


Fig. 1. Sketch of a graphene-based thin-film *a*-Si:H solar cell and geometric structure of SiO₂/ATO/Graphene deposited on top of amorphous silicon thin-film solar cells. hv: Light energy.

In Fig. 1, the thicknesses of amorphous-silicon layer and aluminum electrode are 240 nm and 80 nm respectively which refer to the literature [4]. The ATO layer has a fixed thickness of 20 nm. To assess the performance of the graphene-based thin-film solar cells, it is necessary to know the optical property of graphene. A recent experimental measurement on light transmission through suspended graphene membranes demonstrated that the graphene opacity is a constant independent of the wavelength [5]. Based on the measurement, the complex refractive index of graphene in the visible spectrum was estimated to be $n = 3.0 + iC_1\lambda/3$ with $C_1 = 5.446 \mu\text{m}^{-1}$ [6], which can be useful for accurate prediction of the optical behavior of graphene structures. In our simulated calculation, the graphene layer is presumed to be homogeneous and its thickness is equal to $d = L \times 0.34 \text{ nm}$ [7, 8], where L is the number of graphene layers.

The solar cell is simulated using the finite-difference time-domain (FDTD) method [9, 10], by solving 3D Maxwell's equations with perfectly matched layer boundary conditions for monochromatic, normally incident plane waves. In order to analyze the optical performance of the solar cell, we assume that frequencies ω of the incident waves cover the whole solar spectrum with irradiance $F(\omega)$ corresponding to the AM1.5G standard. The optical data for all the materials used in the simulated calculations are taken from the SOPRA database [11], and the complex refractive index data for amorphous silicon and aluminum are taken from SIAM1.mat and AL.mat respectively. The refractive index of the ATO film layer is 2.01 in the visible spectrum which refer to the literature [12].

In our optical simulations, we calculate the spectral power absorbed by the amorphous silicon layer, defined as follows:

$$Q(\omega) = \frac{\omega \epsilon_0}{2} \int_V \text{Im}[\epsilon(\omega)] \cdot |E|^2 dV \quad (1)$$

In the Eq. (1), the V represents the element volume, characterized by complex and frequency-dependent relative dielectric permittivity $\epsilon(\omega)$, E is the electric field, whose distribution can be obtained in the simulation, and ϵ_0 is the permittivity of free space. What's more, in order to investigate the broadband enhancement of the optical absorption, we calculate the overall power absorbed inside the amorphous silicon layer by integrating the spectral absorbed power $Q(\omega)$ over the AM1.5G solar spectrum, defined as follows:

$$G = \int_{AM1.5G} Q(\omega) d\omega \quad (2)$$

The overall enhancement E then can be calculated using the following equation:

$$E = \frac{G - G(\text{Ref})}{G(\text{Ref})} \quad (3)$$

In the Eq. (3), $G(\text{Ref})$ is denoted for the reference cell with bare ATO transparent electrode.

3. Single factor analysis

To improve the performance of proposed SiO₂/ATO/Graphene structure, a systematic study on the influence of the structural parameters on the efficiency of the enhancement is performed. In this section, we have analyzed single factor influence of structural parameters respectively, including the layer number L for graphene layer and the thickness d for SiO₂ layer.

Firstly, in order to investigate the broadband enhancement of the light trapping, we analyze the dependence of the broadband light-trapping enhancement E on layer number L of graphene, which is depicted in Fig. 2(a). In our optimization, the thickness d of SiO₂ layer is fixed to 80 nm. According to Fig. 2(a), it is seen that there exist optimum value of layer number L for graphene which maximizes the overall broadband enhancement E . This figure reveals that with the increasing of layer number L from 2 to 18, the broadband light-trapping enhancement E firstly increases slowly, and reaches the optimal values of $E = 15.98\%$ when layer number L is 10, then it begins to decrease dramatically. When the layer number L is 12 or higher, its enhancement become negative because majority of incident light has been absorbed by graphene layer themselves.

Moreover, Fig. 2(b) analyzes the dependence of the broadband light-trapping enhancement E on thickness d of SiO₂ layer. In the optimization, the layer number L of graphene is fixed to 10. It is seen that with the increasing of thickness d from 20 nm to 100 nm, the broadband light-trapping enhancement E firstly increases remarkably, then it begins to decrease slowly. When $d = 60 \text{ nm}$, it reaches its optimal values of $E = 16.22\%$. Therefore, the optimization results of Fig. 2(a) and Fig. 2(b) reveal that the control of the layer number L of graphene layer and the thickness d of SiO₂ layer as design parameters can significantly enhance the performance of light trapping for *a*-Si thin film solar cells.

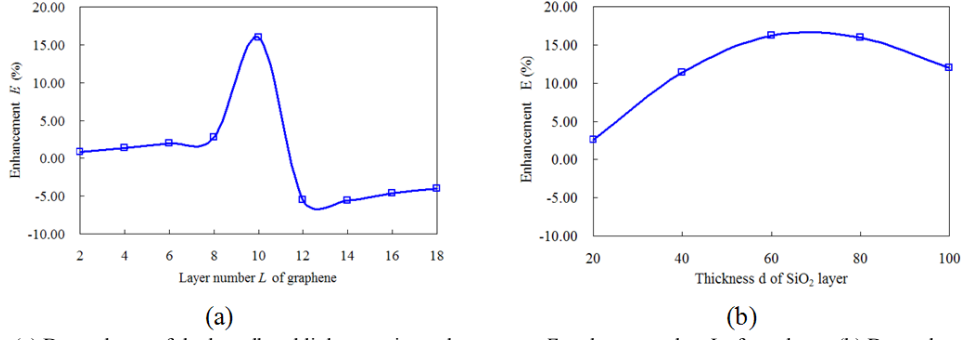


Fig. 2. (a) Dependence of the broadband light-trapping enhancement E on layer number L of graphene. (b) Dependence of the broadband light-trapping enhancement E on thickness d of SiO₂ layer.

4. DE-based design and optimization

To improve the performance of proposed SiO₂/ATO/Graphene structure, a differential evolution (DE) algorithm [13] is employed to optimize the structural parameters in order to enhance the optical absorption of graphene-based α -Si:H thin-film solar cells to the greatest degree. The block diagram of the DE design for parameters optimization of electromagnetic problems has been illustrated in detail in our previous literature [14]. In this paper, the goal of DE is to pursue the optimal structural parameters, including the thickness d for SiO₂ layer and the layer number L for graphene, in order to enhance the optical absorption of graphene-based solar cells to the most degree. Therefore, the fitness function of DE can be defined as follows:

$$\text{Maximize: } E = \frac{G - G(\text{Ref})}{G(\text{Ref})} \quad (4)$$

$$\text{Subject to: } 0 \text{ nm} < d \leq 100 \text{ nm} \quad (5)$$

$$0 < L \leq 20 \quad (6)$$

The optimal solutions of SiO₂/ATO/Graphene structure optimized by DE are listed in Table 1. From the optimization results of Table 1, it is seen that the optimal SiO₂/ATO/Graphene structure can achieve 16.71% enhancement compared to the bare ATO structure when the d is equal to 70 nm and the L is equal to 10.

Table 1. The optimal solutions of SiO₂/ATO/Graphene structure

Structure	d (nm)	L	E
SiO ₂ /ATO/Graphene	70	10	16.71%

To investigate the broadband enhancement performance of the light trapping, we compare the spectral absorption rate of the α -Si:H active region for optimal SiO₂/ATO/Graphene structure and bare 20 nm ATO structure, which is depicted in Fig. 3. Figure 3 clearly illustrates that the proposed SiO₂/ATO/Graphene structure can remarkably enhance the light trapping of thin-film solar cells compared to the bare ATO structure. The optimal SiO₂/ATO/Graphene structure can enhance the optical absorption of silicon for wavelengths above 375 nm which cover the whole violet light spectrum. Therefore, the optimal SiO₂/ATO/Graphene structure almost can enhance the optical absorption of α -Si thin film solar cells in the whole visible and near-infrared wavelength range compared to the conventional bare ATO structure.

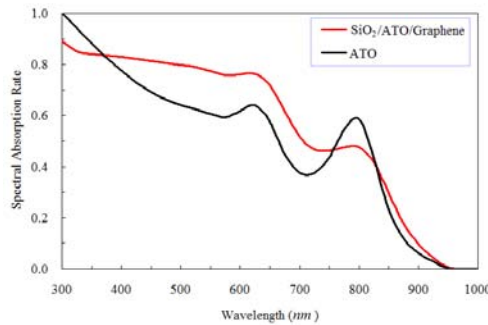


Fig. 3. Spectral absorption rate of the α -Si:H active region as functions of incident wavelength for optimal SiO₂/ATO/Graphene structure and bare 20 nm ATO structure.

Furthermore, in order to investigate the light trapping performance of proposed SiO₂/ATO/Graphene structure, we have also compared its optical absorption enhancements with optimal SiO₂/Graphene/ATO structure. In the SiO₂/Graphene/ATO structure, the graphene coating is deposited between the SiO₂ layer and the ATO layer. The optimization results clearly show that the optimal SiO₂/Graphene/ATO structure can achieve 14.87% enhancement compared to the bare ATO structure when the d is equal to 70 nm and the L is equal to 10. Therefore, it is demonstrated that the optimal SiO₂/ATO/Graphene structure can obtain 16.71% enhancement which has obviously exceeded the light trapping enhancement of 14.87% for the optimal SiO₂/Graphene/ATO.

Figure 4 illustrates the spectral absorption rate of the α -Si:H active region for optimal SiO₂/ATO/Graphene structure and optimal SiO₂/Graphene/ATO. From the comparison results of Fig. 4, it can be seen that the light trapping performance of optimal SiO₂/ATO/Graphene structure is superior to that of optimal SiO₂/Graphene/ATO. The optimal SiO₂/ATO/Graphene structure almost has higher spectral absorption rate in the whole visible and near-infrared wavelength range compared to the optimal SiO₂/Graphene/ATO structure. The reason may be that Graphene has a refractive index n between ATO and α -Si, therefore, the refractive index n of SiO₂, ATO, Graphene and α -Si increases gradually which will achieve a better graded refractive index distribution profile than that of SiO₂/Graphene/ATO structure.

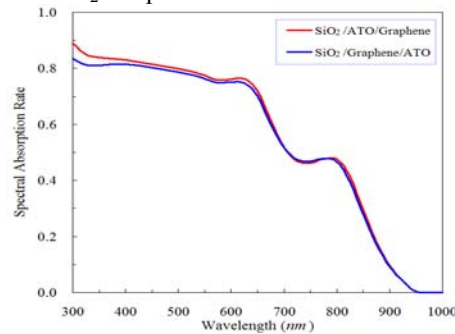


Fig. 4. Spectral absorption rate of the α -Si:H active region as functions of incident wavelength for optimal SiO₂/ATO/Graphene structure and optimal SiO₂/Graphene/ATO structure.

5. Conclusion

In this paper, SiO₂/ATO/Graphene and SiO₂/Graphene/ATO structure are selected for the optimal light-trapping design by using differential evolution method. The effect of graphene is mainly investigated and the thickness of the layers of proposed structure is optimized to enhance the optical absorption of thin-film solar cells to the greatest degree. The optimal SiO₂/ATO/Graphene structure almost can enhance the optical absorption of α -Si thin film solar cells in the whole visible and near-infrared wavelength range compared to the conventional bare ATO structure. Finally, the theoretical calculation results clearly demonstrate that the proposed SiO₂/ATO/Graphene layered structure is obviously superior to the SiO₂/Graphene/ATO structure, and it can obtain a higher light-trapping enhancement in the whole visible and near-infrared wavelength range because of the graded refractive index distribution profile.

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